L Number	Hits	Search Text	DB	Time stamp
1	6	6734029.pn. or 6541354.pn. or 6503570.pn. or 6780465.pn. or 6646662.pn. or 6599582.pn. or 6518087.pn.	USPAT; US-PGPUB	2004/08/12 13:51
2	6	6734029.pn. or 6541354.pn. or 6503570.pn. or 6780465.pn. or 6646662.pn. or 6599582.pn. or 6518087.pn. or US20020114887	USPAT; US-PGPUB	2004/08/12 13:51
3	7	6734029.pn. or 6541354.pn. or 6503570.pn. or 6780465.pn. or 6646662.pn. or 6599582.pn. or 6518087.pn. or "20020114887"	USPAT; US-PGPUB	2004/08/12 13:51
4	40	(Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((silicon or Si) near2 (coat$3 or film or layer or deposit$3)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:10
5	9	((Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((silicon or Si) near2 (coat$3 or film or layer or deposit$3)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and ((active or inactive or pattern$3 or selectiv$4) near5 ($4CVD or (vapor adj deposit$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:10
6	2	(Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((silicon or Si) near2 (coat$3 or film or layer or deposit$3)) and (active with inactive with ($4CVD or (vapor adj deposit$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:05
7	1	(Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) and (active with inactive with (pattern$3 or region or selectiv$5 or $4CVD or (vapor adj deposit$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:12

8	31	((Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((silicon or Si) near2 (coat$3 or film or layer or deposit$3)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) not (((Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((silicon or Si) near2 (coat$3 or film or layer or deposit$3)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and ((active or inactive or pattern$3 or selectiv$4) near5 ($4CVD or (vapor adj deposit$3)))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:06
9	104	(Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((active or inactive or pattern$3 or selectiv$4) near5 ($4CVD or (vapor adj deposit$3)) with (Si or silicon))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:13
11	0	(((Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((active or inactive or pattern$3 or selectiv$4) near5 ($4CVD or (vapor adj deposit$3)) with (Si or silicon))) not ((Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((silicon or Si) near2 (coat$3 or film or layer or deposit$3)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)))) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:12

10	98	((Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((active or inactive or pattern$3 or selectiv$4) near5 ($4CVD or (vapor adj deposit$3)) with (Si or silicon))) not ((Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((silicon or Si) near2 (coat$3 or film or layer or deposit$3)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:12
12	90	(Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and (((active with inactive) or pattern$3 or selectiv$4) near5 ($4CVD or (vapor adj deposit$3)) with (Si or silicon))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:13
13	84	((Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and (((active with inactive) or pattern$3 or selectiv$4) near5 ($4CVD or (vapor adj deposit$3)) with (Si or silicon))) not ((Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((silicon or Si) near2 (coat$3 or film or layer or deposit$3)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:13